

Metal-free circulation type ozonated water generator OWF-C series

OWF-C5L30P

- High concentration ozonated water of 60 ppm
- Suitable for single wafer cleaning process

■ Using a circulation method

- Almost nothing reserved water in piping
- Quickly rising in concentration (**only 1 min**)
- Stable concentration in cleaning process

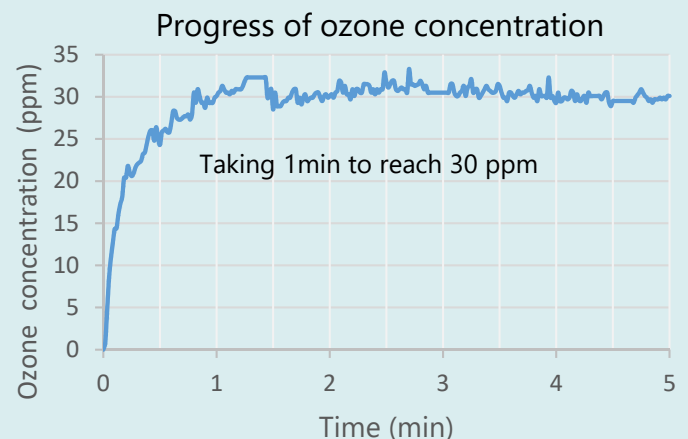
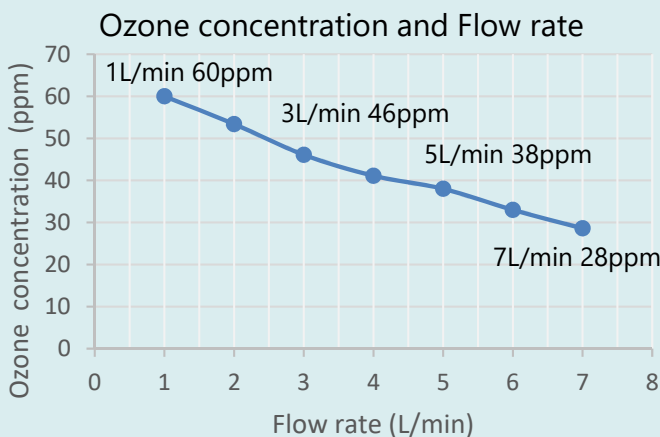
■ Metal-free ozonated water

- Suitable for semiconductor wafer cleaning process by unique technology

■ Small size, light weight, no external supply cooling water

- Size 611W×590D×1317H, Weight 87 kg
- Using radiator for cooling water

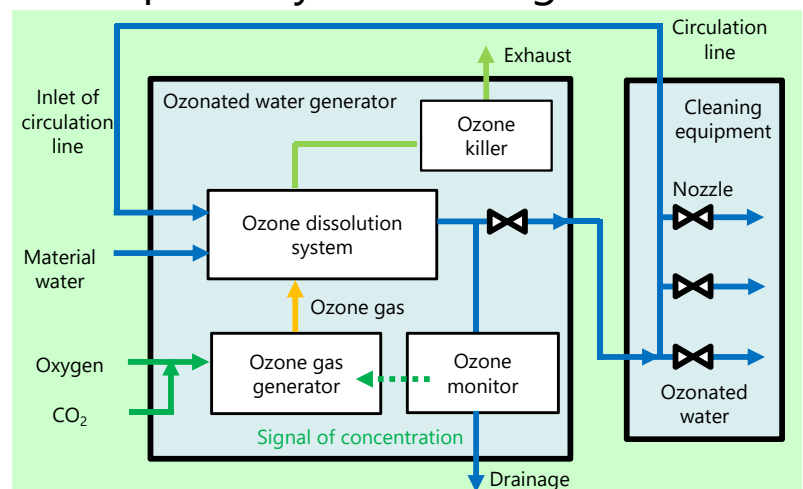
OWF-C5L30P



Specifications

Model	OWF-C5L30P	OWF-C30L30P
Generation method	Silent discharge method	
Cooling method	Radiator circulating water cooling method	
Dissolution method	Injector method	
Ozone monitor	Built-in ultraviolet type ozone monitor	
Ozone concentration in water	MAX 60 ppm	MAX 80 ppm
Flow rate of water	MAX 7 L/min	MAX 50 L/min
Size	611W x 590D x 1317H mm	-
Weight	87 kg	-
Electric power	1 kW	-
Requirement for material oxygen	Pressure: 0.3 MPa, Purity: 99.5 % (Adjustment by CO ₂ or N ₂)	
Requirement for material water	Ultrapure water, D-I water, Tap water Pressure: 0.25 MPa, Temperature: 25°C or less	
Interlock	Water leakage, Abnormally pressure, Ozone leak, Ozone generator trouble	

Example of system configuration



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